



PATENT

Case Docket No. ASMINT.055AUS

Date: November 3, 2003

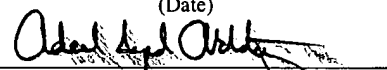
IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s) : Timmermans et al.
Appl. No. : 10/690,215
Filed : October 20, 2003
For : METHOD FOR THE
DEPOSITION OF A
REACTION CHAMBER FOR
THE DEPOSITION OF
SILICON NITRIDE FILMS
Examiner : Unknown
Group Art Unit : Unknown

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

November 3, 2003

(Date)


Adeel S. Akhtar, Reg. No. 41,394

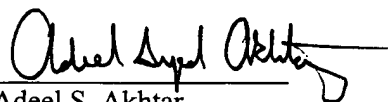
TRANSMITTAL LETTER

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

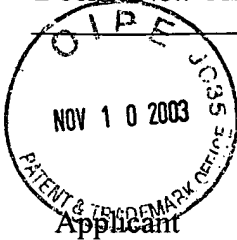
Dear Sir:

Enclosed for filing in the above-identified application are:

- (X) An Information Disclosure Statement.
- (X) A PTO Form 1449 with fifty-seven (57) references.
- (X) Eight (8) references enclosed.
- (X) The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account No. 11-1410.
- (X) Return prepaid postcard.



Adeel S. Akhtar
Registration No. 41,394
Attorney of Record
Customer No. 20,995
(415) 954-4114

**INFORMATION DISCLOSURE STATEMENT**

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Examiner : Unknown
Group Art Unit : Unknown

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing 57 references. Copies of disclosed U.S. patents and/or publications are not included pursuant to PTO waiver of the requirement under 37 C.F.R. § 1.98(a)(2)(i) for applications filed after June 30, 2003. Copies of all other references are enclosed.

This Information Disclosure Statement is being filed with an RCE or within three months of the filing date of this application and no fee is required in accordance with 37 C.F.R. § 1.97(b)(1), (b)(2), or (b)(4).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: October 31, 2003

By: Adeel S. Akhtar
Adeel S. Akhtar
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(415) 954-4114

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
ASMINT.055AUSAPPLICATION NO.
**10/690,215INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT
Timmermans et al.FILING DATE
October 20, 2003GROUP
Unknown

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	1	3,011,006	11/28/61	Nicholson et al.			
	2	3,874,919	4/1/75	Lehman			
	3	4,374,158	2/15/83	Taniguchi et al.			
	4	4,377,347	3/22/83	Hanmyo et al.			
	5	4,389,967	6/28/83	Shimoda et al.			
	6	4,428,975	1/31/84	Dahm et al.			
	7	4,499,354	2/12/85	Hill et al.			
	8	4,522,849	6/11/85	Lewandowski			
	9	4,592,307	6/3/86	Jolly			
	10	4,633,051	12/30/86	Olson			
	11	4,653,428	3/31/87	Wilson et al.			
	12	4,692,556	9/8/87	Bollen et al.			
	13	4,976,996	12/11/90	Monkowski et al.			
	14	4,978,567	12/18/90	Miller			
	15	4,984,904	1/15/91	Nakano et al.			
	16	5,027,746	7/2/91	Frijlink			
	17	5,065,698	11/19/91	Koike			
	18	5,104,514	4/14/92	Quartarone			
	19	5,128,958	7/14/92	Nagashima et al.			
	20	5,246,500	9/21/93	Samata et al.			
	21	5,271,967	12/21/93	Kramer et al.			
	22	5,315,092	5/24/94	Takahashi et al.			
	23	5,336,327	8/9/94	Lee			
	24	5,360,269	11/1/94	Ogawa et al.			
	25	5,421,893	6/6/95	Perlov			
	26	5,456,761	10/10/95	Auger et al.			
	27	5,474,618	12/12/95	Allaire			

EXAMINER

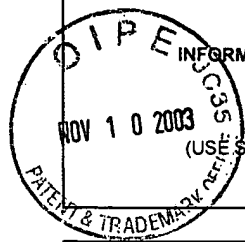
DATE CONSIDERED

*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.

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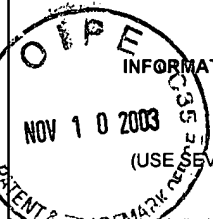
U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	28	5,493,987	2/27/96	McDiarmid et al.			
	29	5,514,439	5/7/96	Sibley			
	30	5,562,774	10/8/96	Breidenbach et al.			
	31	5,571,333	11/5/96	Kanaya			
	32	5,594,482	1/14/97	Ohashi			
	33	5,728,629	3/17/98	Mizuno et al.			
	34	5,788,799	8/4/98	Steger et al.			
	35	5,798,016	8/25/98	Oehrlein et al.			
	36	5,902,407	5/11/99	De Boer et al.			
	37	5,904,778	5/18/99	Lu et al.			
	38	5,910,221	6/8/99	Wu			
	39	6,056,823	5/2/00	Sajoto et al.			
	40	6,066,209	5/23/00	Sajoto et al.			
	41	6,071,573	6/6/00	Koemtropoulos et al.			
	42	6,120,640	9/19/00	Shih et al.			
	43	6,129,808	10/10/00	Wicker et al.			
	44	6,170,429 B1	1/9/01	Schoepp et al.			
	45	6,214,425	4/10/01	Spinelli et al.			
	46	6,227,140 B1	5/8/01	Kennedy et al.			
	47	6,325,857	12/4/01	Miyoshi			
	48	6,325,858 B1	12/4/01	Wengert et al.			
	49	6,342,691 B1	1/29/02	Johnsgard et al.			

EXAMINER

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		FILING DATE October 20, 2003	GROUP Unknown

FOREIGN PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	50	WO 95/31582	11/23/95	PCT				
	51	WO 97/06288	2/20/97	PCT				
	52	WO 99/23276	5/14/99	PCT				
	53	EP 0 229 488	7/22/87	EPO				

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)							
	54	Linke et al., "Behavior of Boron-Doped Graphites, Plasma-Sprayed B ₄ C ₁ and a-C/B:H as Plasma-Facing Materials," <i>Fusion Technology</i> , Vol. 20, (September 1991), pp. 227-230.						
	55	Moslehi et al., "Compositional Studies of Thermally Nitrided Silicon Dioxide (Nitroxide)," <i>J. Electrochem Soc.</i> , Vol. 132, No. 9, pp. 2189-2197 (September 1985).						
	56	Murarka et al., "Thermal Nitridation of Silicon in Ammonia Gas: Composition and Oxidation Resistance of the Resulting Films," <i>J. Electrochem. Soc.</i> , Vol. 126, No. 6, pp. 996-1003 (June 1979).						
	57	Ponnekanti et al., "Failure mechanisms of anodized aluminum parts used in chemical vapor deposition chambers," <i>J. Vac. Sci. Technol.</i> , Vol. 14, No. 3, (May/June 1996), pp. 1127-1131.						

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